HEUCOPHOS® CAPP



in 2K Epoxy

Water based coatings	Heubach formulation No. 993-23		Rev. Number: 01.01	08/21
Function	Product	Producer		PBW
Component A				
Epoxy dispersion	EPI-REZ™ Resin 7520-WD-52	Hexion		31.00
Glycol ether	DOWANOL™ PPh	Dow		2.75
Defoamer	Efka® 2526	BASF		0.25
Premix.				
Anticorrosive pigment	HEUCOPHOS® CAPP	Heubach		8.25
Muscovite mica	MICA SG	Aspanger		0.65
Wollastonite	TREMIN® 283-600 EST	HPF The Mineral Engineers		9.00
Titanium dioxide	Ti-Pure™ R-960	The Chemours Company		9.15
Barium sulfate	Albawhite 80	Sachtleben Minerals		6.10
	Demi. water			7.65
Grind with a bead mill.				
Epoxy dispersion	EPI-REZ [™] Resin 7520-WD-52	Hexion		12.30
Adhesion promoter	CoatOSil™ MP 200	Momentive		0.80
Add while stirring.				
			=	87.90
Component B				
Curing agent	EPIKURE™ Curing Agent 6870-W-53	Hexion		11.30
Flash rust inhibitor	HEUCOFLASH™ LQ2	Heubach		0.80
Add while stirring.	·			
			=	12.10
				12.10
Mix components A and B	B thoroughly prior to use.			

100.00

Specifications				
Vol% Anticorrosive pigment reg. pigment/filler	30.8			
PVC in %	29.7			
PVC / CPVC	0.5			
Solids in %	61.7			
Crosslinking in %	60.0			

Gf-WB02_034-01_01A

Our application information and any other information in this document as well as our product specifications are based on our current state of knowledge at the Revision Date mentioned in the respective document. They are non-binding and cannot be taken as a guarantee. The processing company must establish the suitability of individual products itself. As their use lies beyond our knowledge and control, we cannot accept any liability relating to the use of our products in particular applications. In addition to that, the legal rights of third parties must always be considered. The product specification agreed between the customer and ourselves is the basis upon which our general sales and delivery conditions are set and is the deciding factor concerning any liabilities. Our standard specification is then valid if no specification has been agreed upon between the customer and ourselves.